




Embedded Passives

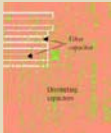


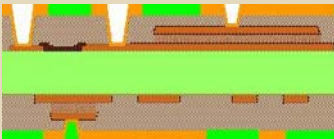
Packaging Paradigm of the Future?





Jason Ferguson
NSWC Crane
November 10, 2010






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1



Embedded Passives

Outline

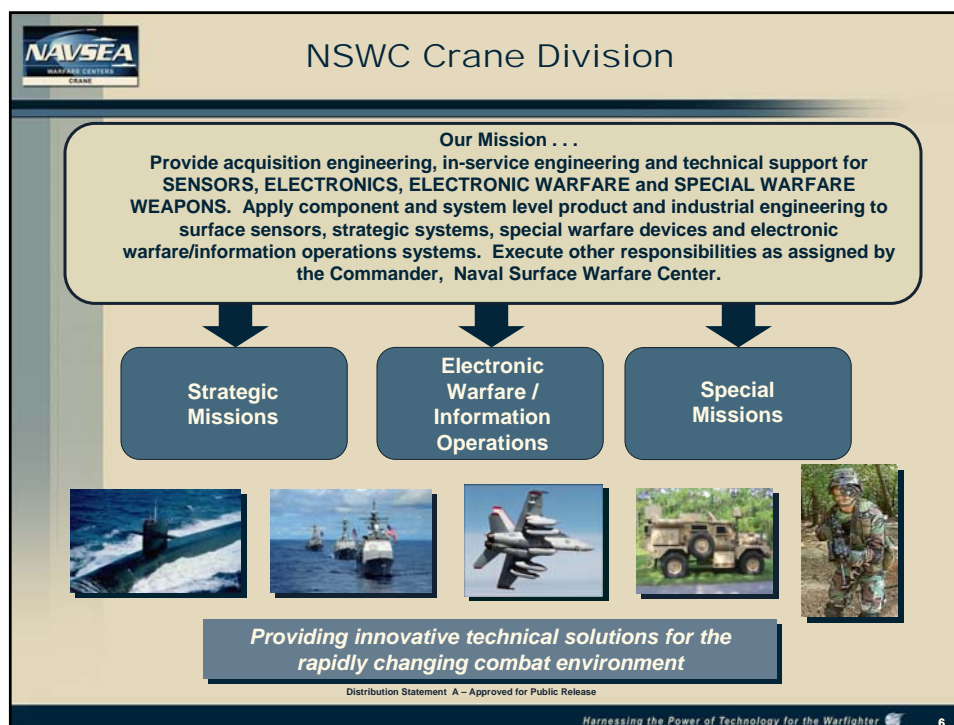
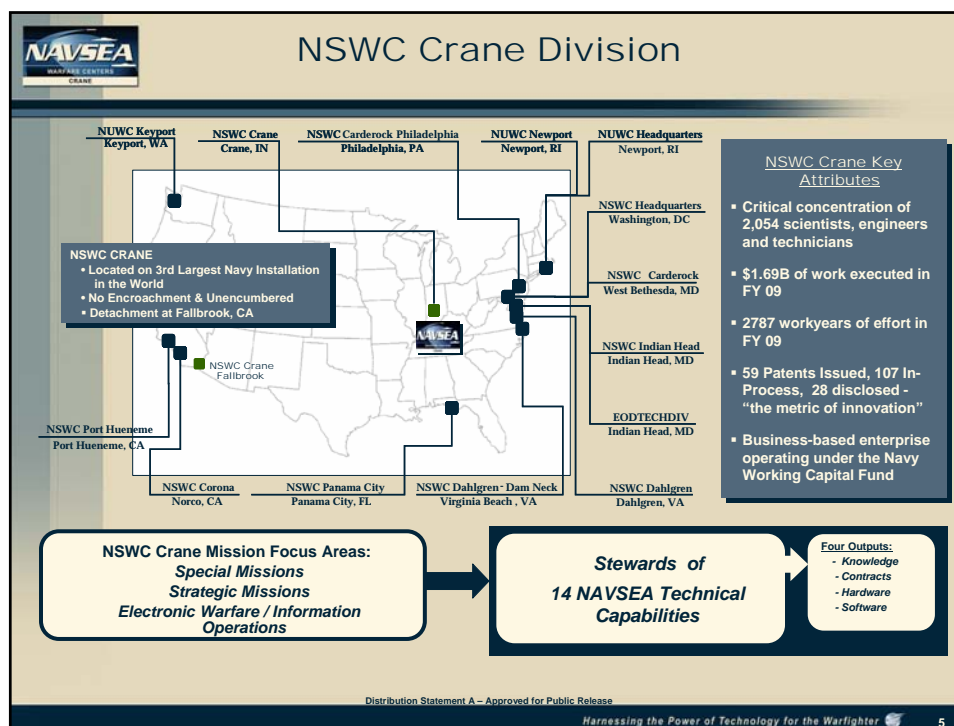
- Overview of Crane
- Embedded Passives: What are they?
- Benefits of EP Technology
- What is slowing the adoption of EP Technology?
- EP Materials
- Emulator Project: Lessons Learned

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2







Strategic Missions Products and Thrust Areas

<p>Crane provides a broad range of systems engineering expertise for the sustainment and modernization of the Land Based, Sea Based and Space Based Ballistic Missile Early Warning Sensors</p> <p>Threat Detection</p>	<p>Every AEGIS BMD platform carries key components either designed, developed, tested or sustained at NSWC Crane.</p> <p>MDA lead for Anti-Tamper technologies</p> <p>Integrated Missile Defense</p>
<p>Experts in advanced missile technology, NSWC Crane leads the way in the design, development, production and sustainment of ballistic missile electronics</p> <p>Global Strike</p>	<p>DoD resource for Critical Product Technologies including High Reliability, Radiation Hardened Electronics, Power Sources, High Power RF Devices and Printed Wiring Boards</p> <p>Critical Technology Innovation Center</p>

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8



Leadership

- DoD Executive Agent Microwave Devices
- DoD Executive Agent for Printed Circuit Boards
- STANDARD Missile Battery Technical Direction Agent for Power Systems
- CGX Acquisition Missile Defense Radar System Engineering Lead
- Leadership in Hardened Electronics And Radiation Technology
- Missile Defense Agency (MDA) Lead for Anti-Tamper Technology

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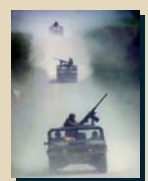
Strategic Missions Capabilities

<ul style="list-style-type: none"> • Over 800 Technical Professionals • 210,000 Sq Ft of StM Facilities • World's most Powerful LINAC • Premier facilities for FA/MA • Full spectrum power system facility • High power radar module facility • Anti-tamper laboratory • Critical Technology Innovation Center (CTIC) 	<ul style="list-style-type: none"> • Flight Engineering • Radiation Science Technology • Acquisition Engineering • Missile Defense Components • Power & Energy Solutions • Failure & Materials Analysis • Advanced RF Systems • Anti-tamper Science • Modeling and Simulation of Electronics
Resources	Services
<div style="display: flex; justify-content: space-between;"> <ul style="list-style-type: none"> • Alliant Tech Systems • Boeing • Lockheed Martin • Raytheon • Indiana University <ul style="list-style-type: none"> • Penn State University • Purdue University • Texas A&M • Vanderbilt University </div>	<ul style="list-style-type: none"> • Advanced Electron-Photo Facility • Hubble Telescope batteries • SBX Radar Transition • PrCB Executive Agent • CWI TWT test capability
Partners	Recent Successes

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Electronic Warfare/ Information Operations Products and Thrust Areas	
<p>• Crane is a Center of Excellence for EW & has worked Electronic Attack Systems for the past 30 years.</p>  <p>• Crane develops <u>ALL</u> infrared counter-measures for US Navy & USMC aircraft.</p>  <p>Air</p>	<p>• Crane provides Technical Warrant Holder & Systems Engineering leadership for spiral development programs to keep pace with evolving ASMD threats.</p> <p>• Crane provides comprehensive T&E services and facilities to reduce costs associated with spiral developments.</p>  <p>Maritime Surface</p>
<p>• Crane is a EW Virtual ISEA Team Member and lead for EW capability enhancements.</p>  <p>• Crane is NAVSEAs Technical Warrant Holder for Submarine ELINT.</p> <p>Maritime Subsurface</p>	<p>• Crane designed, developed and fielded electromagnetic environment (EME) systems for various organic test ranges. Provides realistic Mod & Sim Environment for in the loop System Testing</p> <p>• Crane provides CREW systems engineering, installation & in-theater support in reducing Counter-IED casualties</p>  <p>Ground</p>

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12




Leadership

- **NATO IRCM and Seeker Exercise Support**
- **DoDs Largest EW Footprint - Only government facility that is multi-spectral/multi-domain**
- **COMOPTEVFOR Trusted Agent for Surface Ship EW Test & Evaluation**
- **OPNAV Next Generation Jammer AoA Technical IPT Lead**
- **Navy Network Warfare Command (NNWC) EWIIP Technology IPT Lead**
- **ONR Next Generation Jammer Airborne Electronic Attack (AEA) Principal Investigator**
- **Naval EW Technology Integration Center (NEWTIC):**
 - The Navy's Technology Transition Agent to the Fleet

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EW / IO Capabilities

<ul style="list-style-type: none"> • 1,588 Skilled Personnel • 320,000 sq ft EW Complex • Secure MILCON facilities • Naval EW Technology Integration Center • Information Operations Range • Unique Nulka Round Assembly Facility 	<ul style="list-style-type: none"> • EW Modeling & Simulation • Threat Analysis & Effectivity testing • Anti-Ship Missile Defense • Intelligence, Surveillance & Reconnaissance Support • Airborne Infra-Red Countermeasures • Electro-Optics/Infra-Red System Support • Systems Engineering • EW Modeling & Simulation
Resources	Services
<ul style="list-style-type: none"> • Naval Research Lab • Air Force Research Lab • Army Research Lab • Purdue • Penn State • Ohio State University • Georgia Tech Research Institute • Numerous OEMs 	<ul style="list-style-type: none"> • AN/SLQ-32(V) General Receiver Improvement Program Concept Demonstration • JCREW Fielding • JCREW 3.1 Field Operational Assessment in OEF • JCREW 3.3 Preliminary Design Review • CEASAR Testing
Partners	Recent Successes

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Special Missions Products and Thrust Areas

<p>Crane designed, built and fielded the first Counter-Sniper Enclosure for USAF Force Protection HMMWVs in 6 weeks</p> <p>Mobility & Maneuverability</p>	<p>Crane is USSOCOM's PM for the development, acquisition, fielding and sustainment of the SOF Combat Assault Rifle (SCAR)</p> <p>Special Munitions & Weapons</p>
<p>Crane integrates sensors on a variety of ground platforms for special missions</p> <p>Sensors & Communications</p>	<p>To date Crane has provided Small Arms operations & maintenance training to 1641 personnel</p> <p>Training</p>

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16




Leadership

- **Joint & Special Operations Program Management Office**
 - Project Management support for USSOCOM, ASAF,USN and USMC
- **Advanced Systems and Concepts (AS&C) TRUSTED AGENT for Non-Traditional Assessments & Technology Transition for Office of Secretary of Defense (OSD)**
- **Electro-Optics (EO) & Infrared (IR) Sensing Systems Leadership**
- **Small Arms and Weapons Technical Leadership**
- **Extensive Multi-Site Testing Capability**
 - Camp Atterbury
 - Muscatatuck Urban Training Center (MUTC)
 - Multi-Site Ordnance Test Complex, Hawthorne, NV
 - Special Weapons Assessment Range
 - Glendora Lake Test Facility

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Special Missions Capabilities

<ul style="list-style-type: none"> • Extensive test facilities for expeditionary warfare, electro-optics, environmental, weapons and ballistics • Over 1.3M sq ft of RDT&E facilities • 720 person government workforce • Realistic Ground Range Facility • EO / IR Test Facility <p>Resources</p>	<ul style="list-style-type: none"> • Weapons, Sensors & Comm platform Integration • Small Arms Weapons and Integration • Rapid Standard and Non-Traditional Testing and Assessment Capability • Broad In-Theater Support Capability • Laser Test & Evaluation • Pyrotechnics / Demolition Product Support <p>Services</p>
<ul style="list-style-type: none"> • Indiana National Guard • Naval Research Lab • US Army Night Vision & Electronic Sensors Directorate • Penn State, Purdue • Marine Corps Programs Office, Hawthorne, NV • Joint Services Small Arms Synchronization Team • Multiple Industry Partners <p>Partners</p>	<ul style="list-style-type: none"> • Mobile Technology Complex • Shipboard Protection System • Non-Traditional Test JCTDs • Completed Electro-Optic Technology Roadmap • 235,000 weapons accessories fielded to date <p>Recent Successes</p>

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Technical Assignments

NAVSEA Technical Warrants

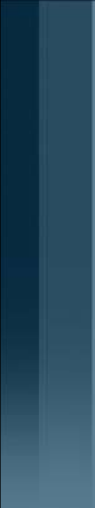

Electro-Optics (EO) & Infrared (IR) Sensing Systems (except submarines)
Anti-Tamper Implementation
Electronic Warfare and SIGINT Programs (including Ground EW and Intelligence Collection Equipment)
Small Arms and Weapons
Shipboard Anti-Terrorism and Force Protection

DOD Executive Agent

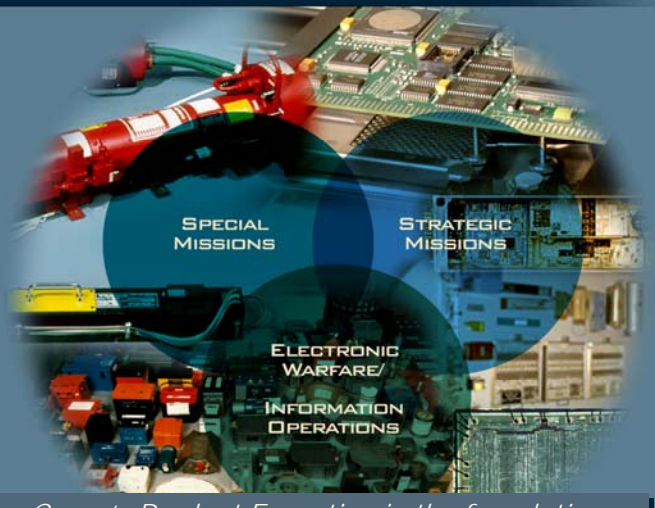
Microwave Power Tube Industry
Printed Circuit Board Technology

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PRODUCT EXPERTISE . . . SECOND TO NONE




*Crane's Product Expertise is the foundation
for our Focus Areas*

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Product Expertise




Crane provides cradle to grave power system engineering services for ship, air, land, and space based systems

Power Systems



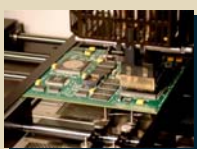
Unique and comprehensive Printed Circuit Board development, manufacturing, test, and evaluation capabilities

Electronic Interconnect Technology



Crane is DoD's largest and most capable battery evaluation facility with a unique abusive test facility and extensive environmental capabilities

High Energy Test Facility




Navy's *ONLY* Printed Circuit Board manufacturing facility and one of only two facilities in DoD

Electrochemistry Eng Facility

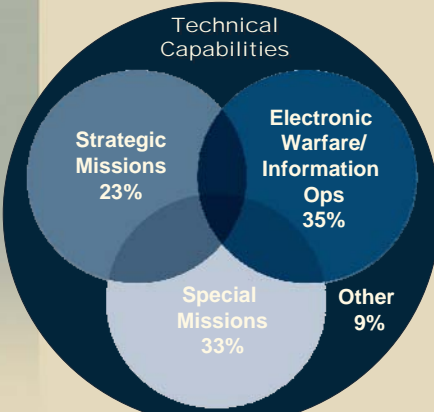
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Technical Capabilities Supporting NSWC Crane Focus Areas

Providing innovative technical solutions for the rapidly changing combat environment



Focus Areas/Workyears

Technical Capabilities

- Strategic Systems Hardware
- Special Operations Hardware
- Electronic Warfare Systems
- Radar Components
- Energy & Power Sources
- Microwave Technologies
- Microelectronic Technologies
- Infrared Countermeasures & Pyrotechnics
- Defense Security Systems
- Electro-Optic Systems
- Obsolescence Management
- Conventional Ammunition
- Acoustic Sensors
- Navy Electronics Depot

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Summary

- NSWC Crane is critical to the Department of Defense, providing technical engineering solutions and total lifecycle leadership for many of the systems that protect and enable our Warfighters
- NSWC Crane's total focus is to support the Warfighter by leveraging our technical capabilities to provide innovative, leading-edge technical solutions for the rapidly changing combat environment
- Our employees honor the Crane core values to provide the diverse knowledge, skills and abilities to support the installation's technical capabilities
- This team of skilled professionals puts technical solutions directly into the hands of the Warfighter, ensuring safer missions and saving lives while practicing continuous process improvement every day
- NSWC Crane supports the NAVSEA Goals of building an Affordable Future Fleet, Sustaining Today's Fleet Efficiently and Effectively, and by Enabling our People.



Keeping America's Navy #1 in the World


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Embedded Passives

What are they?




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Embedded Passives



What are they?

Passive Components


- Resistors and capacitors (for this discussion)
- Provide/absorb energy
 - Maintain constant V or A
- Filter signals
- Control impedance
- Sense signals
- Delay or synchronize signals




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25



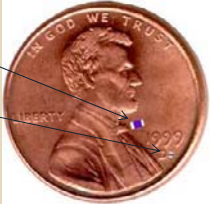
Embedded Passives



Where are they?

0402 resistor:
• (It's the same size as President Lincoln's bow tie)

0201 capacitor:
Now inspect 2000 parts like this on one board.



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26

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Embedded Passives

Embedding Passives – Another Evolutionary Step

The diagram illustrates the evolutionary steps of passive components in PCB design. It shows three cross-sectional views of a substrate. The top view, labeled 'Through Hole', shows components with leads inserted into holes in the substrate. The middle view, labeled 'Surface Mount', shows components with leads soldered to the surface of the substrate. The bottom view, labeled 'Embedded Passives', shows components built directly into the substrate layers. A dashed line connects the three views, indicating the progression. Text to the right of the bottom view states: 'Build components directly into the substrate to reduce footprint'. A small credit line at the bottom right reads: '<< Courtesy of Richard Ulrich >>'. At the bottom of the slide, it says 'Distribution Statement A: Approved for Public Release' and 'Harnessing the Power of Technology for the Warfighter' with a logo and the number 27.

Through Hole

Surface Mount

Embedded Passives

Build components directly into the substrate to reduce footprint

<< Courtesy of Richard Ulrich >>

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Embedded Passives

Let's Start with Resistors

The flowchart categorizes resistor manufacturing processes. It starts with two main categories: 'Thin-films' and 'Thick-films'. 'Thin-films' is further divided into 'Sheet' and 'Plated'. 'Sheet' is further divided into 'Plated', 'Vacuum Deposit', and 'Sputtered'. 'Plated' under 'Thin-films' is further divided into 'Electrolytic NiP' and 'Electroless NiP'. 'Vacuum Deposit' is further divided into 'Ni Cr and Ni Cr Al Si'. 'Sputtered' is further divided into 'Pt'. 'Thick-films' is further divided into 'PTF' and 'Polymer'. At the bottom of the slide, it says 'Distribution Statement A: Approved for Public Release' and 'Harnessing the Power of Technology for the Warfighter' with a logo and the number 28.

Thin-films

Thick-films

Sheet

Plated

PTF

Plated

Vacuum Deposit

Sputtered

Electrolytic NiP

Electroless NiP

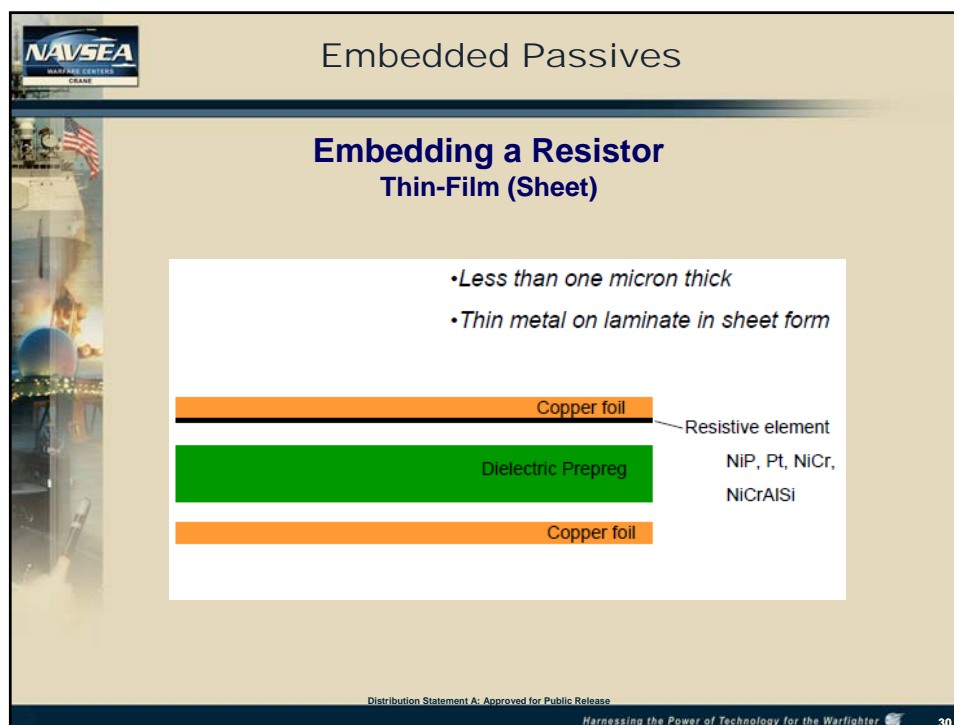
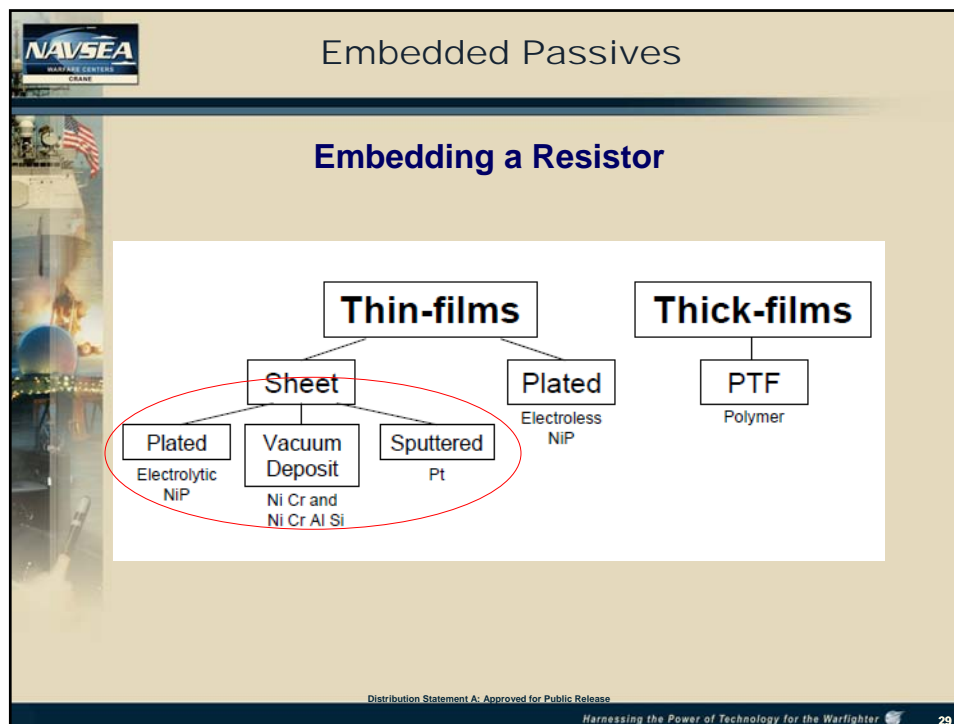
Ni Cr and Ni Cr Al Si


Pt

Polymer

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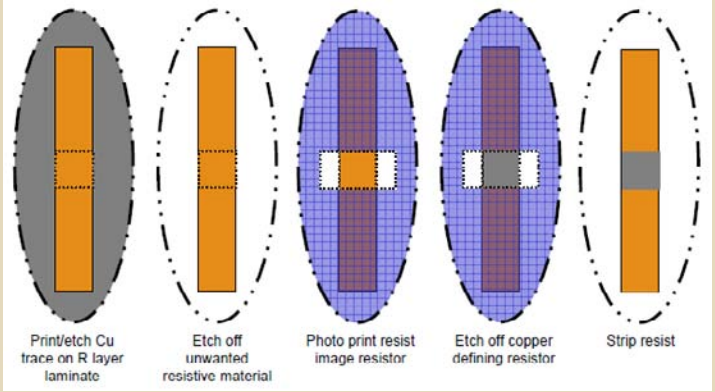
Harnessing the Power of Technology for the Warfighter 28





Embedded Passives

Embedding a Resistor Thin-Film (Sheet)



Print/etch Cu trace on R layer laminate

Etch off unwanted resistive material

Photo print resist image resistor


Etch off copper defining resistor

Strip resist

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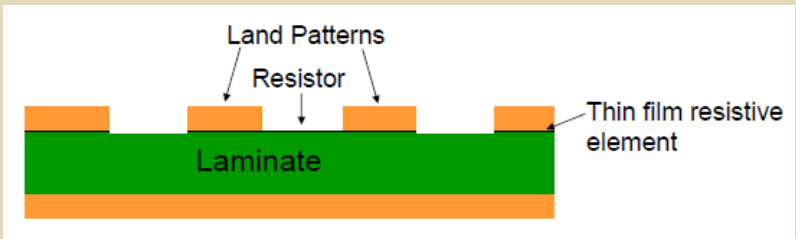
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31



Embedded Passives

Embedding a Resistor Thin-Film (Sheet)



Land Patterns

Resistor


Laminate

Thin film resistive element

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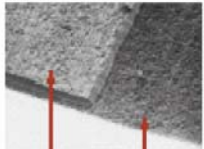
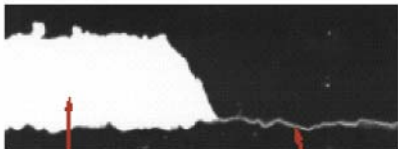
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32




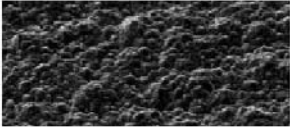
Embedded Passives

Embedding a Resistor Thin-Film (Sheet)



Copper foil land pattern Resistive element

Copper foil land pattern Resistive element



Surface of copper foil with thin-film resistive element


Resistor

Ticer Technologies

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33



Embedded Passives

Embedding a Resistor

Thin-films

- Sheet
 - Plated
Electrolytic
NiP
 - Vacuum Deposit
Ni Cr and
Ni Cr Al Si
 - Sputtered
Pt
- Plated
Electroless
NiP


Thick-films

- PTF
Polymer


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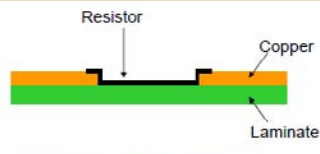
34



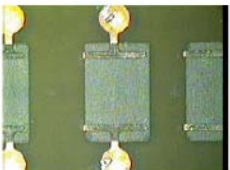
Embedded Passives



Embedding a Resistor Thin-Film (Plated)



Laser trimmed resistor
(courtesy of ESI)




Plated resistor (courtesy of Mcrux)


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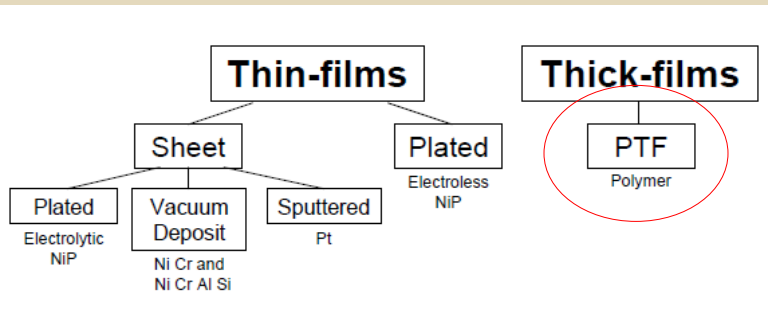
35



Embedded Passives



Embedding a Resistor




```
graph TD
    Thin-films --> Sheet
    Thin-films --> Plated1[Plated]
    Sheet --> Plated2[Plated]
    Sheet --> Vacuum[Vacuum Deposit]
    Sheet --> Sputtered[Sputtered]
    Plated1 --> Electroless[Electroless NiP]
    Plated2 --> Electrolytic[Electrolytic NiP]
    Vacuum --> NiCr[Ni Cr and Ni Cr Al Si]
    Sputtered --> Pt
    Thick-films --> PTF[PTF]
    PTF --> Polymer[Polymer]
```

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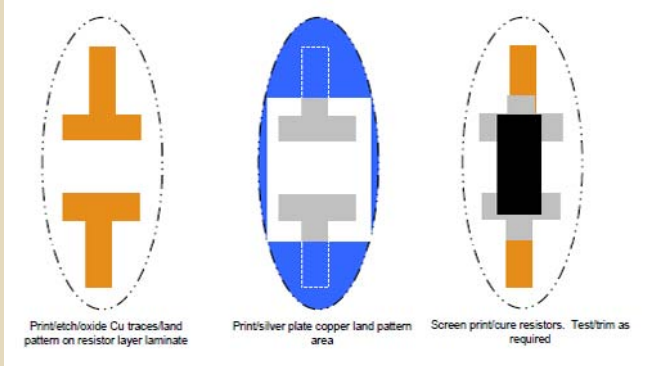
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36



Embedded Passives

Embedding a Resistor Polymer Thick Film



Print/etch/oxide Cu traces/land pattern on resistor layer laminate


Print/silver plate copper land pattern area

Screen print/cure resistors. Test/trim as required

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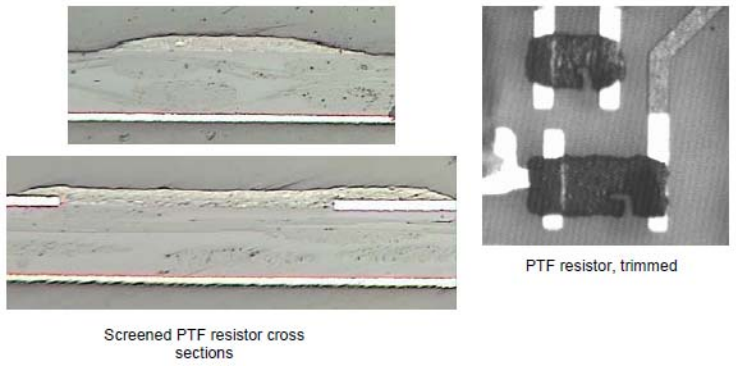
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37



Embedded Passives

Embedding a Resistor Polymer Thick Film




Screened PTF resistor cross sections

PTF resistor, trimmed


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38

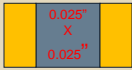


Embedded Passives

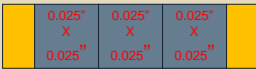


How to achieve a value?

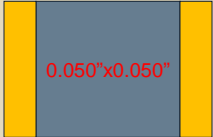
- Resistor material is specified in Ohms per square (OPS)
- The more squares in a series, the larger the resistance value in Ohms.
- Assume 50 OPS mat'l (and a perfect square)



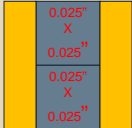
= 50 Ohms



= 150 Ohms





= 50 Ohms




= 25 Ohms

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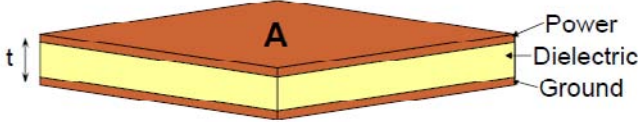


Embedded Passives



Now, let's look at capacitors

Parallel planes in PCBs – a very common situation





$$C = \frac{A \cdot D_k \cdot K}{t}$$

Where:

- C = Capacitance (Farads)
- A = Area of plates
- D_k = Dielectric constant of material between plates
- K = Constant
- t = Thickness between plates

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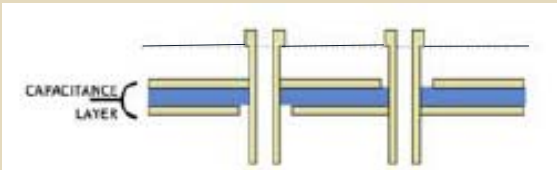
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Embedded Passives

Embedded Capacitor


Distributed or Planar



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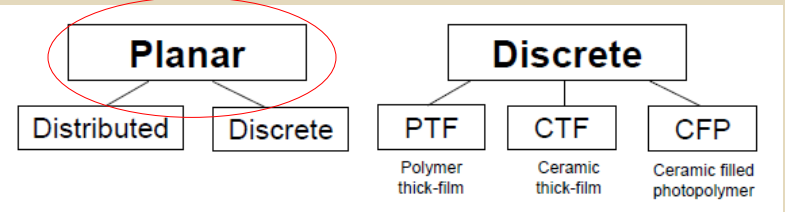
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41



Embedded Passives

Embedding a Capacitor



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42

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Embedded Passives

Embedded Capacitor Planar

Discrete

Filter capacitor

Distributed

Decoupling capacitors

Courtesy AEPT

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43

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Embedded Passives

Embedding a Capacitor

```
graph TD
    Planar[Planar] --> Distributed[Distributed]
    Planar --> Discrete[Discrete]
    Discrete --> PTF[PTF  
Polymer thick-film]
    Discrete --> CTF[CTF  
Ceramic thick-film]
    Discrete --> CFP[CFP  
Ceramic filled photopolymer]
```

Planar

Discrete

Distributed

PTF
Polymer thick-film


CTF
Ceramic thick-film

CFP
Ceramic filled photopolymer

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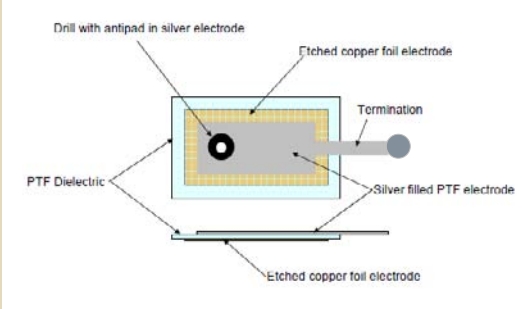
44



Embedded Passives

Embedded Capacitor Discrete (Polymer Thick Film)


- Screen printing process
 - Very similar to PTF resistors
 - PTF Dielectric screened on previously etched copper electrode and cured (bottom capacitor plate)
 - PTF Silver filled conductor screened on dielectric and cured (top capacitor plate)



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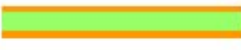


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45



Embedded Passives


Embedded Capacitor Discrete (Ceramic Filled Photodielectric)

-  Doubled sided core or MLB subcomposite
-  Coat with CFP and laminate copper foil
-  Print and etch mezzanine electrode

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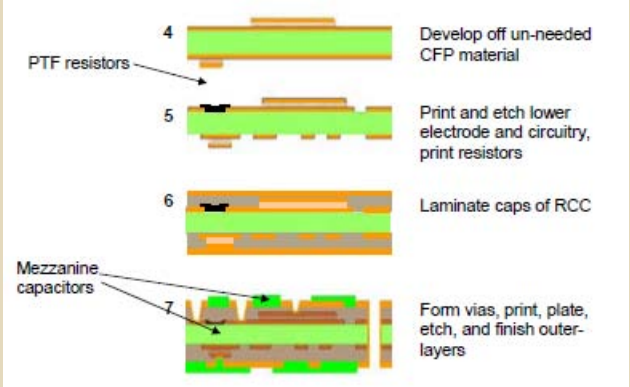
46



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Embedded Capacitor Discrete (Ceramic Filled Photodielectric)



4 Develop off un-needed CFP material

5 Print and etch lower electrode and circuitry, print resistors

6 Laminate caps of RCC

7 Form vias, print, plate, etch, and finish outer-layers


PTF resistors

Mezzanine capacitors

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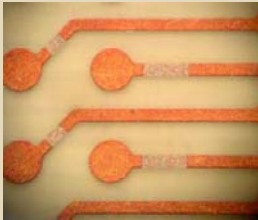
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Benefits of EP Technology




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Benefits

- Frees Up Real Estate on the Surface, Which Means
 - More IC space, possible added functionality
 - Or reduction in size of the board
 - More boards per panel in manufacturing
- Improved performance
 - Reduction in loop inductance
 - Reduction in EMI
- Reliability
 - Less solder joints to SMT passives
 - Less vias
- Cost
 - Fewer parts to mount


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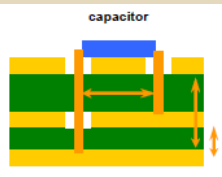


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Benefits in Performance

- Large Electrolytic Capacitors
 - Lower impedance at lower frequencies
 - Parasitic inductance makes them have higher impedance at higher frequencies
- Small surface-mount caps
 - Less capacitance
 - Higher Z at lower F
 - Less inductance
 - Lower Z at higher F
- Board plane capacitance
 - Even less capacitance, less inductance
 - Less vias to connect to SMT parts means less inductance attributed to vias
 - Eliminates mounting inductance of SMT parts




capacitor


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Power Distribution Network Benefits of Plane Capacitance

- Only means of reducing board PDN impedance at higher frequencies
- The future will have higher operating frequencies
- Can increase capacitance by
 - Increase in plane size
 - Increase Dk between planes
 - Decrease distance between planes


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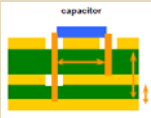


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Benefits with HDI


- Less vias going through entire board
 - Smaller reduction in copper on planes from via antipads
 - Antipads reduce plane capacitance
- More copper available to deliver current
- Vias closer together, planes closer to caps
 - Less inductance for decoupling capacitors
- Planes closer together
 - Larger embedded board capacitance
 - Use of special dielectric materials



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What is slowing the adoption of EP Technology?



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Barriers

- Software Computer Aided Design Tools
 - Mentor Graphics
 - Zuken
- Tolerancing
 - SMT can achieve $\pm 0.01\%$
 - Embedded have to fight to achieve $\pm 1.0\%$
- Maintainability
 - Incapable of repair
- Standards
- Manufacturability

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Standards

- IPC – 4821 Specification for Embedded Passive Device Capacitor Materials
- IPC – 4811 Specification for Embedded Passive Device Resistor Materials
- IPC – 2316 Design Guide for Embedded Passive Device Printed Boards
- IPC – 6017 Qualification and Performance Specification for Printed Boards Containing Embedded Passives
- IPC – 2227 Sectional Design Standard for Embedded Passive Printed Boards (**under construction**)

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Manufacturability

- Most boardshops will not want to invest without big return on investment
- Boardshops will have to learn
 - How to scale resistors
 - How to panelize and assign nomenclature to layers
 - Handling of thin core materials that are <16 um thick
 - Laser trimming of resistors
 - Possibly new process chemistries

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Manufacturability (Scaling Resistors)

- CAM operators will scale the designed resistors
- Purpose: Achieve a final post-manufactured resistance value that meets design spec
- What will change resistance value in manufacturing?
 - Trimming (of course)
 - Surface Treatment, prior to lamination (alt oxide, black oxide, etc)
 - Multilayer Lamination
 - Hot Air Solder Level or Reflow

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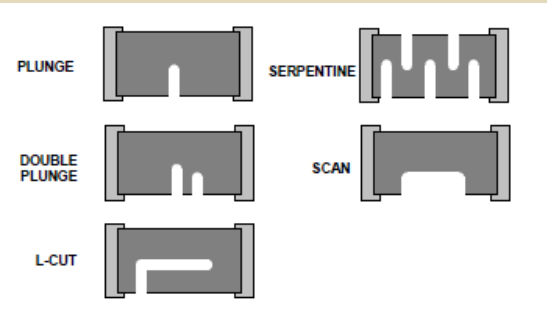
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Trimming




The diagrams illustrate five different resistor trimming techniques:

- PLUNGE**: A rectangular resistor with a single U-shaped notch cut into its bottom center.
- DOUBLE PLUNGE**: A rectangular resistor with two U-shaped notches cut into its bottom, one near each end.
- L-CUT**: A rectangular resistor with a single L-shaped notch cut into its bottom left corner.
- SERPENTINE**: A rectangular resistor with a complex, multi-toothed notch cut into its bottom center.
- SCAN**: A rectangular resistor with a wide, shallow U-shaped notch cut into its bottom center.


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EP Materials



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Resistor Material Suppliers

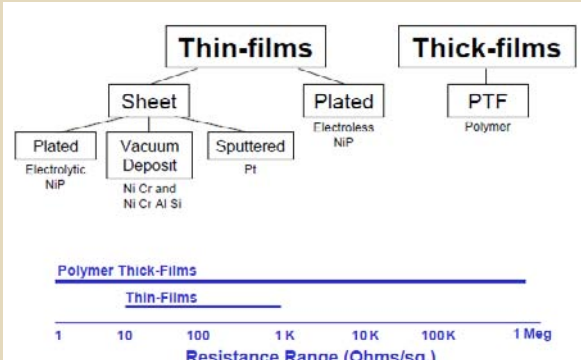
Photo-print and etch		
Thin-film		
	Ohmega Industries - OhmegaPly	10, 25, 100 & 250 ohms/sq
	Rohm & Haas - Insite	500 & 1000 ohms/sq
	Ticer Technologies	25, 50, 100, 250 & 1000 ohms/sq
Photo-print and plate		
Thin-film		
	MacDermid - M Pass	25 to 100 ohms/sq
Screen-print		
Polymer thick-film (PTF)		
	Electra, Asahi & others	1 ohm to 1 megohm/sq
	DuPont - Interra	1 to 10,000 ohms/sq

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Resistor Materials




Polymer Thick-Films


Thin-Films

1 10 100 1 K 10 K 100 K 1 Meg

Resistance Range (Ohms/sq.)

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Thin-Film Resistor Materials

Properties of Thin-Film Resistors in PCB Substrates						
Resistance	Sheet resistance tolerance	CV (coefficient of variance)	TCR (temperature coefficient of resistance)	Solder float	Temperature exposure	Humidity exposure
(Ω/nominal)	(%)	(%)	-85° C to +125° C (ppm/°C)	(%Δ R) after 20 sec @ 260°C	(%Δ R) after 1000 hrs @ 70°C	(%Δ R) after 240 hrs @ 40°C and 95% RH
10	+/-3	+/-3	-5	-0.02	NA	0.25
25	+/-5	+/-5	-50 to 110	0.5	0.5	0.5
50	+/-5	+/-5	-60	0.75	0.75	0.75
100	+/-5	+/-5	-80	1.0	1.0	1.0
250	+/-10	+/-10	100	0.5	1.0	2.0
500	+/-10	NA	100	NA	NA	NA
1000	+/-10	NA	100	NA	NA	NA


Note: Properties vary depending on the resistive material, foil used, resistor value range, aspect ratio, type of substrate, termination design, and other manufacturing conditions. Reported data is limited. The above is a summary extracted from technical articles and vendor data sheets.

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Embedded Passives




Polymer Thick-Film Resistor Materials


Properties of Polymer Thick-Film Resistors in PCB Substrates

Resistance range	Sheet resistance tolerance	CV (coefficient of variance)	TCR (temperature coefficient of resistance)	Solder dip	Temperature exposure	Humidity exposure	Humidity exposure
(Ω)	(%)	(%)	~30° C to +100° C (ppm/°C)	(% Δ R) after 3X260°C	(% Δ R) after 1000 hrs @ 100°C	(% Δ R) after 1000 hrs @ 40°C and	(% Δ R) after 500 hrs @ 85°C and
10 to 100	+/-10	2 to 6	250	-2 to 2.5	0 to -2.5%	0 to 2%	-3 to 5%
10K to 1Meg	+/-10	2 to 8	750	-5 to 2.5	0 to -5%	0 to 5%	0 to 5%


Note: Properties vary depending on the material source, resistor value range, thickness, aspect ratio, cure, type of substrate, termination design and finish, and other manufacturing and design conditions. Reported data is limited. The above is a summary extracted from several technical articles and vendor data sheets.

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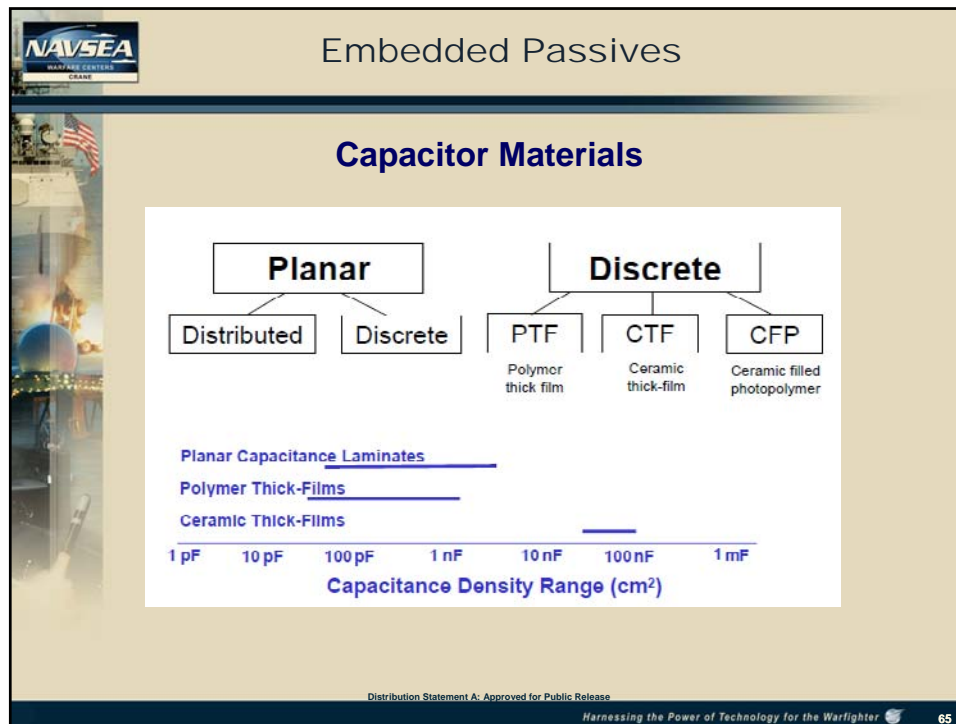


Capacitor Material Suppliers

Planar	
Unfilled and filled dielectrics	
SCI-Sanmina (licensor) - BC2000	78 & 140 pF/sq cm
3M - C-Ply	850 pF/sq cm
Oak-Mitsui - FaradFlex	155 to 1700 pF/sq cm
DuPont - Interra HK	125 to 700 pF/sq cm
Ticer Technologies	110 & 215 pF/sq cm
Discrete (Screen print)	
Polymer thick-film (PTF)	
Electra - ElectraQD'OR	75 to 3,000 pF/sq cm
Ceramic thick-film (CTF) (Soon to be commercialized)	
DuPont - Interra EPC	93,000 pF/sq cm
Discrete (Photo image)	
Unfilled and filled dielectrics	
Any of the planar materials	See above
Ceramic filled photodielectric (CFP)	
Motorola (licensor) - Mezzanine	1,550 pF/sq cm

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Planar Capacitor Materials

Properties of Planar Laminate Capacitor Materials for PCB Substrates


Property	Units	Method	Property range (*)
Dielectric thickness	μ	Nominal	8 to 50
Capacitance density @ 1MHz	nF/in ²	IPC TM 650 2.5.5.3	0.5 to 11
	pF/cm ²		78 to 1700
Dk @ 1 MHz		IPC TM 650 2.5.5.5	4.4 to 30
Loss tangent @ 1 MHz		IPC TM 650 2.5.5.5	0.003 to 0.02
Dielectric strength	KV/mil	IPC TM 650 2.5.6.3	1.2 to 7.3
Electrical migration (85°C, 85%RH, 35V)	Hours		>1000
HiPot (VDC)			100 to 500

(*) this represents the ranges of 14 different products manufactured by 5 companies


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PTF Discrete Capacitor Materials

PROPERTY	UNITS	TYPICAL VALUE	TEST METHOD
Dielectric thickness	milis	0.5 - 1	NA
Capacitance	nF/in ²	0.5 - 20	NA
Dielectric constant	--	4 - 60	ASTM-D-150
Loss tangent	--	NA	NA
Dielectric strength	V/mil	>1000	ASTM-D-149
Temperature coefficient of capacitance	%	NA	NA
Bias test: 85%RH/85°C/5V/1000hr	Pass/Fail	NA	NA
Insulation resistance	Ohms	>10 ¹²	JIS Z 3197
Temperature coefficient of expansion	ppm / °C	NA	NA


Note: Technical reports and data for PTF capacitors is very limited. The above information was compiled from supplier data sheets.

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Emulator Project

Lessons Learned

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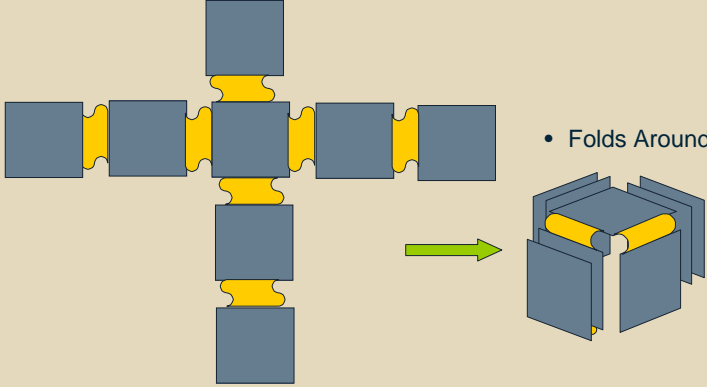
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Embedded Passives

JPL Emulator

- Eight Petal Rigid Flex Design
- Motor Controller Board



- Folds Around Motor

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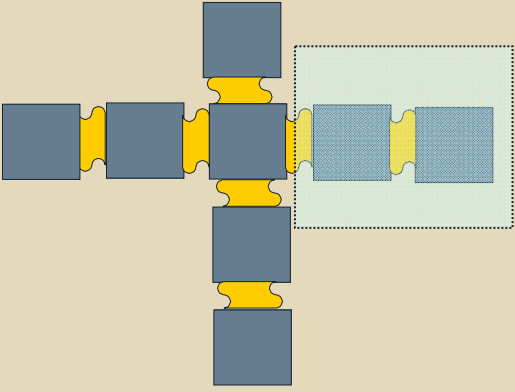
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JPL Emulator


- Two petals selected to redesign




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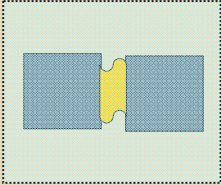


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JPL Emulator


- Objectives:
 - Maintain same layer count (12)
 - Reduce number of decoupling capacitors, while maintaining or decreasing noise
 - Possibly reduce area
 - Embed resistors
 - Maintain electrical performance




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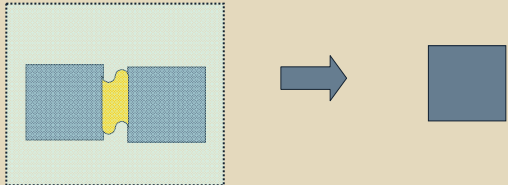
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JPL Emulator




From two

To one

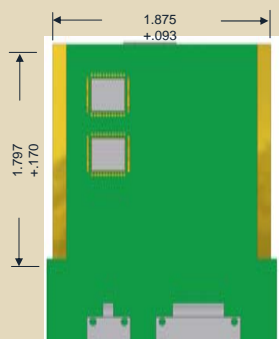
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72

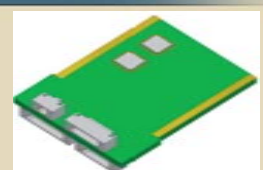
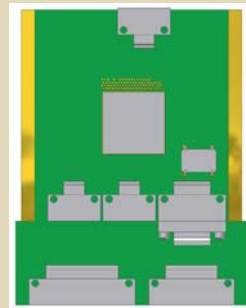


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**JPL Emulator
Design Concept**

Side A





Side B

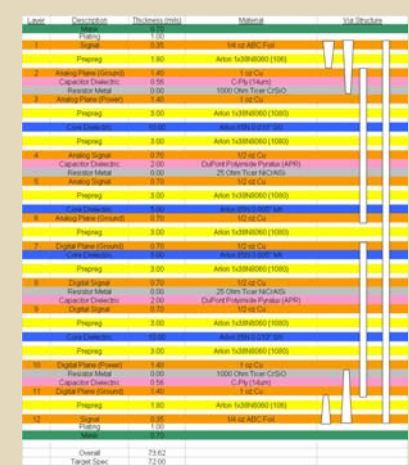
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Stackup A (with 3M C-Ply)

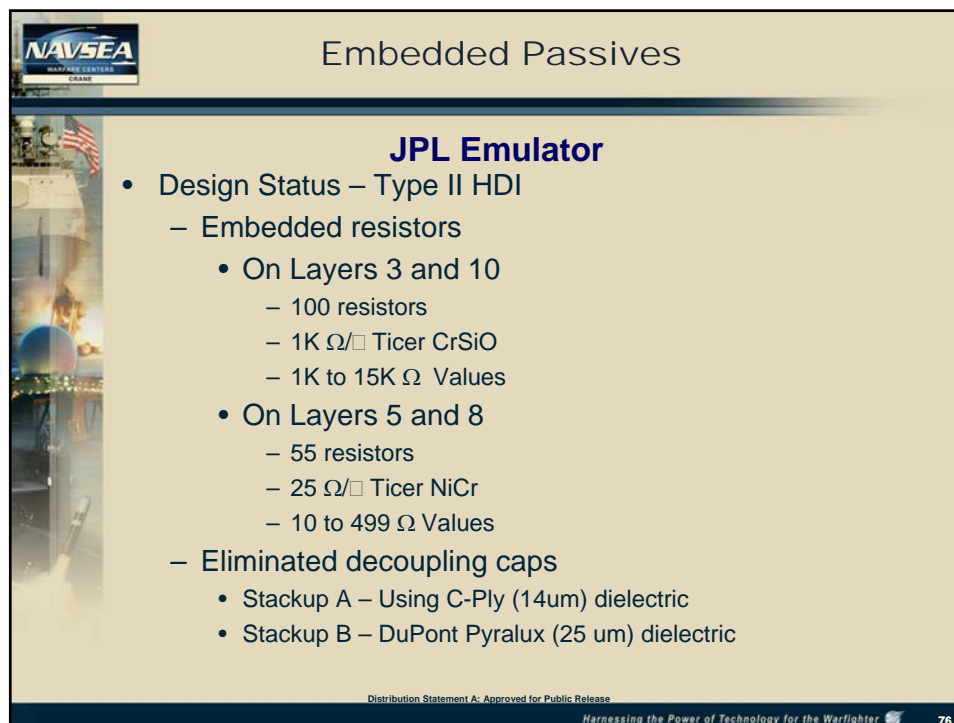
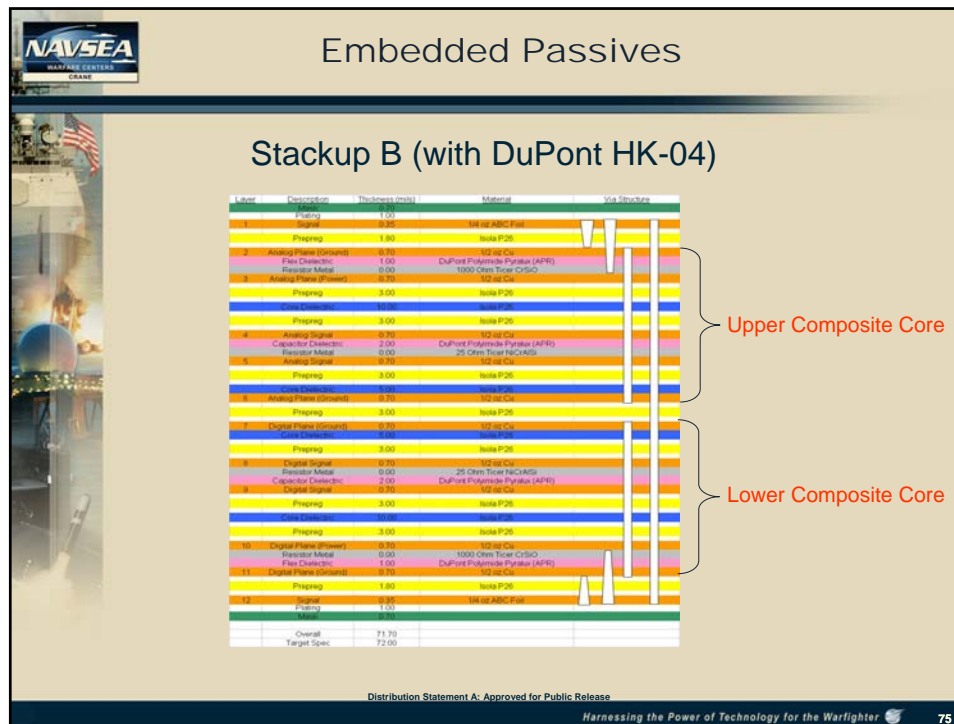
Upper Composite Core

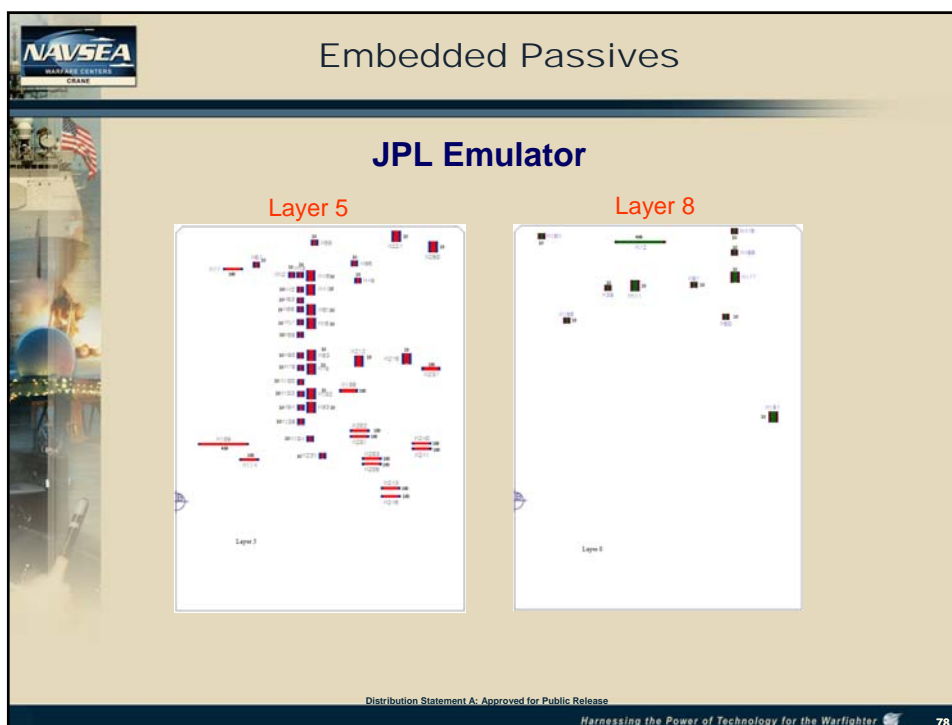
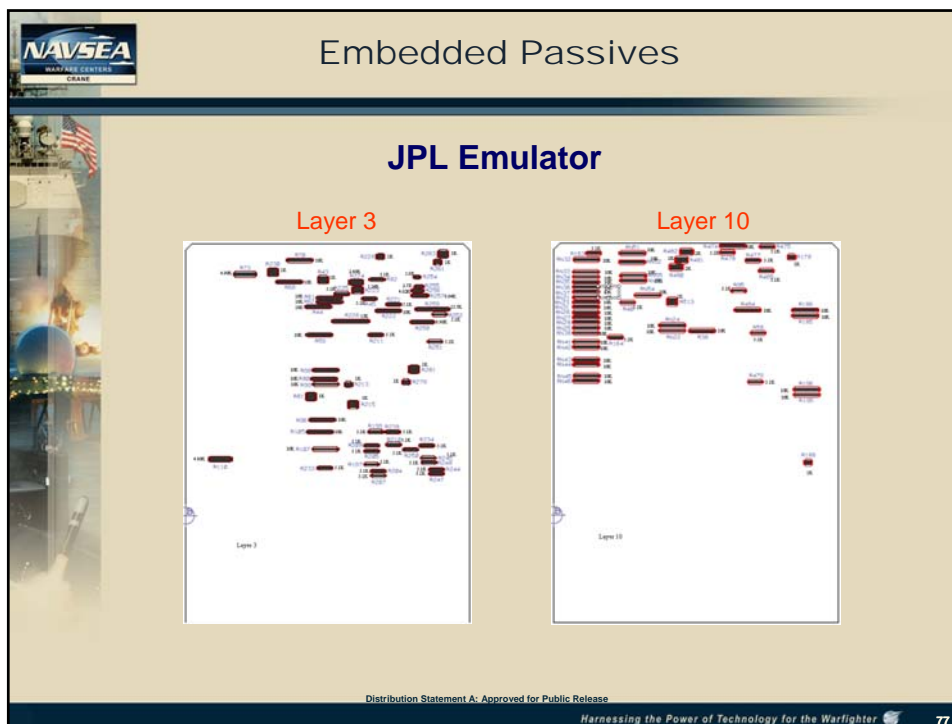
Lower Composite Core



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JPL Emulator

- Design Lessons Learned
 - Do not locate resistors directly under IC's (great possibility of increasing inductance loop because of circuits return path)
 - Pay attention to resistor power ratings
 - Enlarged 10 Ohm resistors with 0.2 Watt rating
 - Maintain surface bulk capacitors for low and midrange frequencies to dampen noise
 - Add contingent capacitors at corners of ASIC
 - Design software does not compensate resistors

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Embedded Passives


JPL Emulator

- Fabrication Lessons Learned
 - Stagger board patterns on panel
 - Copper etching compensation factors
 - Resistivity variations of materials
 - Alternative Oxide effects
 - Compensation due to material movement
 - Geometry compensation for trimming
 - Resistance change during lamination
 - Resistance change during reflow
 - Drilling parameters


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Embedded Passives




JPL Emulator

- Panelization
 - Stagger boards
 - Include resistor coupons
 - Local scaling of laser drill
 - Scaling of resistor geometries
 - Compensating layers


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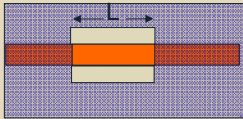



Embedded Passives



JPL Emulator


- Cu Etch Compensation
 - Grow trace widths by
 - .0010" for L3 and L10
 - .0009" for L5 and L8
 - Reduce length of resistor mask by
 - .001" for L3 and L10
 - .0015" for L5 and L8




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Embedded Passives




JPL Emulator

- Resistivity variations on materials
 - C-Ply ~1000 OPS
 - DuPont ~1300 OPS
 - For the two stackups
 - Resistor geometries (length and width) between the two materials on L3 and L10 will be different in order to compensate for this variation in resistivity
 - Changed in CAM


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83




Embedded Passives



JPL Emulator

- Alternative Oxide Effects
 - Rise in resistance due to lengthening of resistor
 - NiCr w/0.5 oz Cu – increase of 0.3 to 0.8 mils
 - CrSiO w/0.5 oz Cu – increase of 0.9 to 1.7 mils
 - Predictable
 - Copper is microetched at both ends of resistor
 - Resistor metal is unharmed by etchant
 - For wide resistors, values are less affected




Microetched copper


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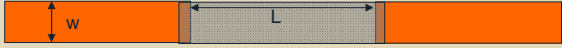
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JPL Emulator


- Alternative Oxide
 - Wide resistor's value is less affected

Wide Resistor	$R = \rho \times \frac{L}{w}$	Narrow resistor
$w = 0.100"$		$w = 0.015"$
$L_0 = 0.100"$		$L_0 = 0.015"$
$L_1 = 0.1008"$		$L_1 = 0.0158"$
$\rho = 50 \Omega/\square$		$\rho = 50 \Omega/\square$
$R_0 = 50.0 \Omega$		$R_0 = 50.0 \Omega$
$R_1 = 50.4 \Omega$		$R_1 = 52.7 \Omega$




Microetched copper

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Embedded Passives




JPL Emulator

- Scaling Due to Material Movement
 - Contributors
 - Etching material
 - Lamination
 - Results after 1st lamination
 - Layers 4/5 and 8/9
 - Grow layers by 430 ppm (x and y)
 - Layers 2/3 and 10/11
 - DuPont HK-04
 - » Grow layers by 1235 ppm (x and y)
 - 3M C-Ply
 - » Grow layers by 910 ppm (x and y)

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Embedded Passives



JPL Emulator


- Resistor geometry compensation for trimming
 - Layer 5 and Layer 8 (25 OPS NiCr)
 - Target 80% of final value
 - Layer 3 and Layer 10 (1300 OPS CrSiO on HK04)
 - Target 50% of final value
 - Layer 3 and Layer 10 (1000 OPS CrSiO on C-Ply)
 - Target 70% of final value

(Purpose: Hopefully, allow all resistors to be created to a value that is less than pre-surface treatment value)


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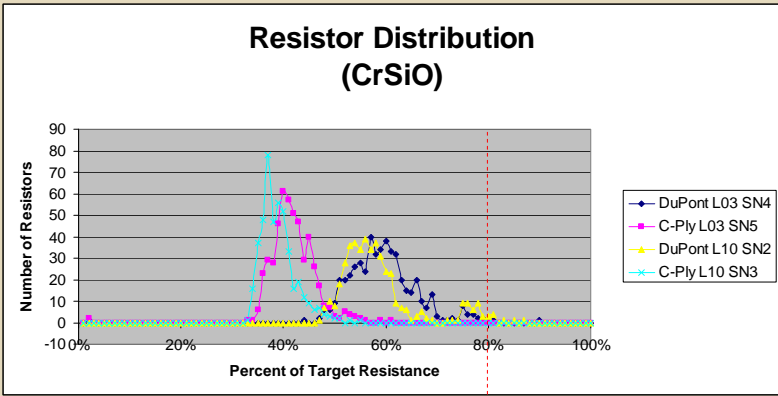


Embedded Passives



JPL Emulator

Resistor Distribution (CrSiO)




Percent of Target Resistance	DuPont L03 SN4	C-Ply L03 SN5	DuPont L10 SN2	C-Ply L10 SN3
35%	0	0	0	80
40%	0	60	0	40
50%	0	10	0	10
60%	40	0	0	0
70%	30	0	0	0
80%	10	0	0	0
90%	5	0	0	0


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88



Embedded Passives




JPL Emulator

- Resistance Change Due to Lamination
 - Layer 5 and Layer 8 (25 OPS NiCr)
 - No change
 - Layer 3 and Layer 10 (1300 OPS CrSiO on HK04)
 - 1.5 percent increase
 - Layer 3 and Layer 10 (1000 OPS CrSiO on C-Ply)
 - 1.5 percent increase


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89



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JPL Emulator

- Resistance Change Due to Reflow
 - Layer 5 and Layer 8 (25 OPS NiCr)
 - 0.1 to 0.2 percent increase
 - Layer 3 and Layer 10 (1300 OPS CrSiO on HK04)
 - 1.1 percent increase
 - Layer 3 and Layer 10 (1000 OPS CrSiO on C-Ply)
 - More testing needed (one data set, to date)


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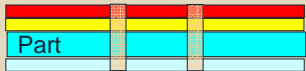


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JPL Emulator

- Mechanic Drill Parameters (L2-L6 and L7-L11 cores)
 - Speed – 110,000 rpm
 - Infeed – 23 in/min
 - Retract rate – 300 in/min
 - Entry material
 - Bulls-eye material
 - .005" FR-4
 - Exit material - Slickback




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Embedded Passives



JPL Emulator

- Resistor Stages


CrSiO on HK04 Layer 3 or Layer 10 example

Stage	Etched	Trimmed	Surface Prep	Lamination	Reflow
Percent change	-	+20 to +220	+1.5	+1.5	+1.1
Resistance (Ohms)	3,000 to 8,000	9598	9745	9891	10,000

Layer 5 or Layer 8 example

Stage	Etched	Trimmed	Surface Prep	Lamination	Reflow
Percent change	-	+8 to +39	+1.5	0	+1.1
Resistance (Ohms)	70 to 90	97.4	98.9	98.9	100

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Embedded Passives



Acknowledgments

- Richard Snogren
- Parker Lee
- Happy Holden
- Dave Burgess
- Dan Brandler
- John Andresakis
- Joel Peiffer
- Dave McGregor
- Richard Ulrich


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93



Embedded Passives



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94